

AZ 12XT – run sheet

Merck

[nanyte.com/photoresists/az-12xt](https://www.merck.com/content/az-12xt) · last updated 2026-07-26

Thickness: 3–20 μm

Softbake: 110 °C (95–110 °C) · 2 min · hotplate

Post-exposure bake: 90 °C (90–100 °C) · 60 s

Develop: Developer AZ 300MIF · Dilution 0.26N (2.38%) TMAH,
ready-to-use · Method puddle

Hardbake: 100–115 °C